

Docket Number: 081468-0356680

PATENT APPLICATION

Client Reference: P-1823.020-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

HANS VAN DER LAAN, et al.

Group Art Unit: UNKNOWN

Application No.: 10/590,352

Examiner: UNKNOWN

Filed: August 23, 2006

Confirmation No.: 8164

For: METHOD TO DETERMINE THE VALUE OF PROCESS PARAMETERS BASED
ON SCATTEROMETRY DATA

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

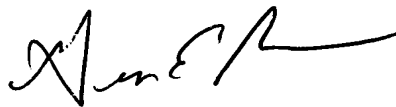
Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Copies of non-patent literature are included. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicants respectfully request the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicants with the next Office communication to indicate that the references have been considered, per MPEP § 609.

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

PILLSBURY WINTHROP SHAW PITTMAN LLP



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FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office

Atty.
Dkt. No.

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Client Ref.

081468

0356680

P-1823.020-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: VAN DER LAAN et al.

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Date: May 21, 2007

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of

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Examiner: Unknown

Group Art Unit: Unknown

U.S. PATENT DOCUMENTS

| Examiner's Initials* | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
|-------------------------|--------------------|-----------------|---|-------|--------------|------------------------------------|
| | AR | | | | | |
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| | CR | | | | | |
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| | ER | | | | | |
| | FR | | | | | |
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| | HR | | | | | |
| | IR | | | | | |

FOREIGN PATENT DOCUMENTS

| | Document Number | Date MM/YYYY | Country | Inventor Name | English Abstract | | Translation Readily Available | |
|--|--------------------|-----------------|---------|---------------|---------------------|----|-------------------------------------|----|
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| | JR | | | | | | | |
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OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

| | | | | | |
|----|--|--|--|---|--|
| TR | Allgair et al., "Spectroscopic CD Offers Higher Precision Metrology for sub-0.18 μ m Linewidth Control", Yield Management – Yield Acceleration Strategies for the Semiconductor Industry", Vol. 4, Issue 2, Summer 2002, pp. 8-13 | | | X | |
| UR | Wold et al., "Nonlinear PLS Modeling", Chemometrics and Intelligent Laboratory Systems", 7, pp. 53-65 (1989) | | | X | |
| VR | Valley et al., "Approaching New Metrics for Wafer Flatness: An Investigation of the Lithographic Consequences of Wafer Non-Flatness", Metrology, Inspection, and Process Control for Microlithography XVIII, Proceedings of SPIE, Vol. 5375 (2004) | | | X | |
| WR | | | | | |
| XR | | | | | |
| YR | | | | | |

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.